



G00002

ABSTRACT OF THE DISCLOSURE
COMPOSITIONS FOR PREPARING LOW DIELECTRIC MATERIALS

Low dielectric materials and films comprising same have been identified for
5 improved performance when used as performance materials, for example, in interlevel dielectrics integrated circuits as well as methods for making same. In one aspect of the present invention, the performance of the dielectric material may be improved by controlling the weight percentage of ethylene oxide groups in the at least one porogen.

10



162162

Figure 1

N:\DOCNOS\06200-06299\06294P\US\Appl\06294P USA.doc